

ION SOURCE

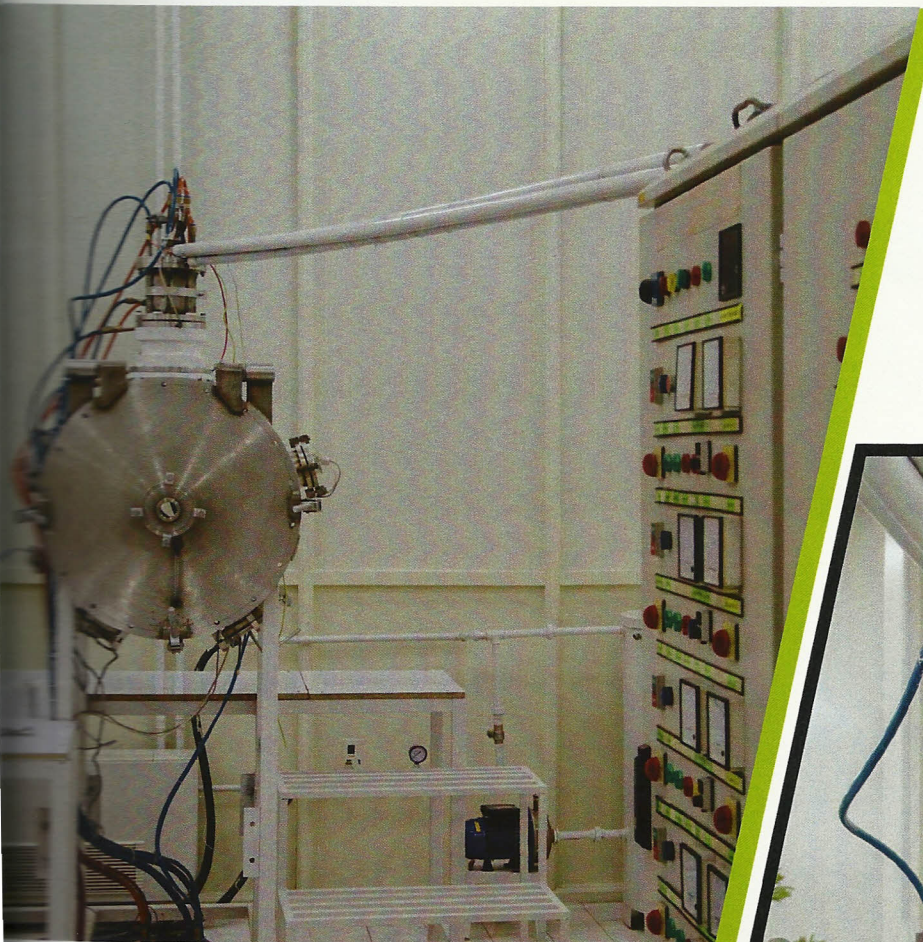
SPECIFICATIONS

Gases: Ar, N₂,...

Ion Beam Current (For Ar): 50 mA

Maximum Ion Energy: 10 KV

Beam Diameter: 5 cm



Ion Source with regard to their characteristics beam are used in different surf treatments. Such as surface etching or ion implantation. They can also be used for depositing thick or thin layers on different substrates.

This ion source system was designed and fabricated by our staffs in 2004 for this purpose.

